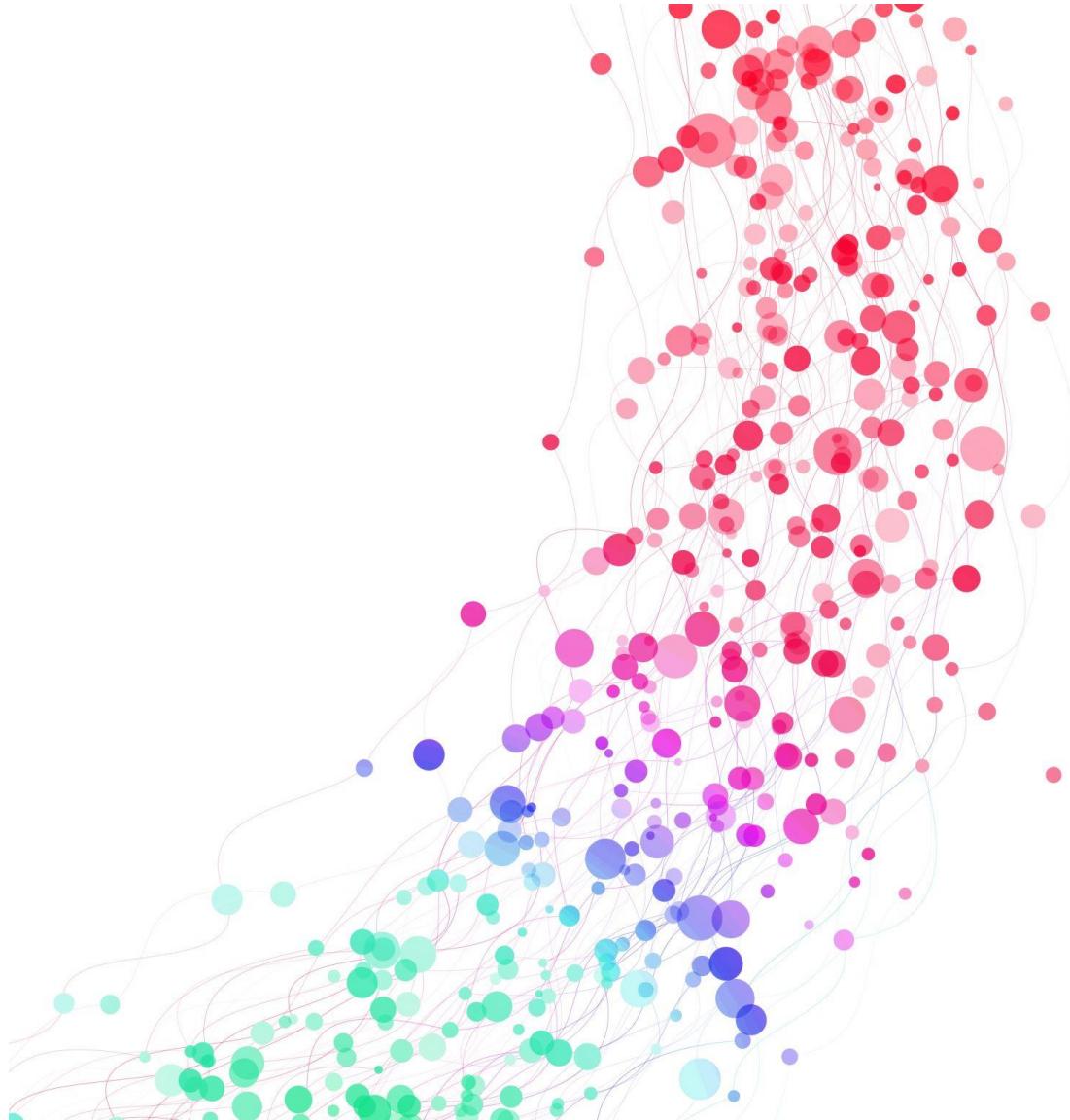
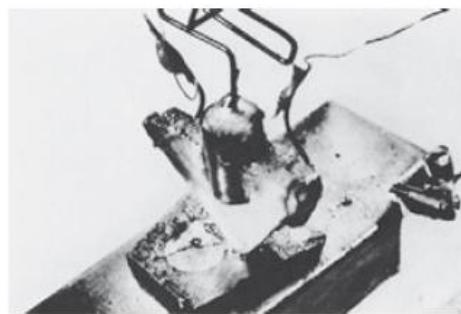


Fundamentals of Electronics

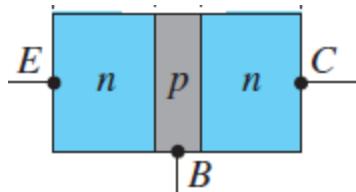
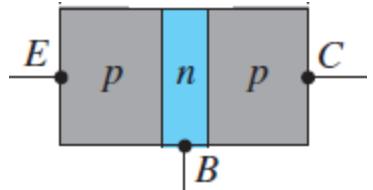
ECE 101



# Bipolar Junction Transistor (BJT)

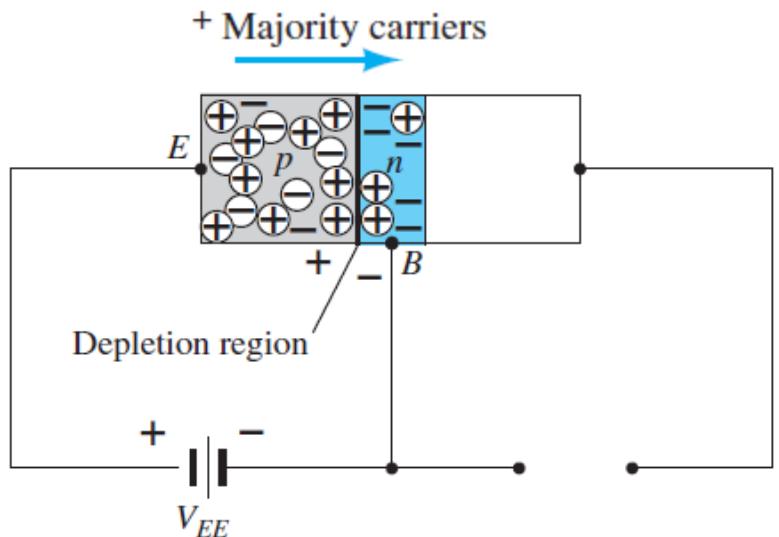


The first transistor

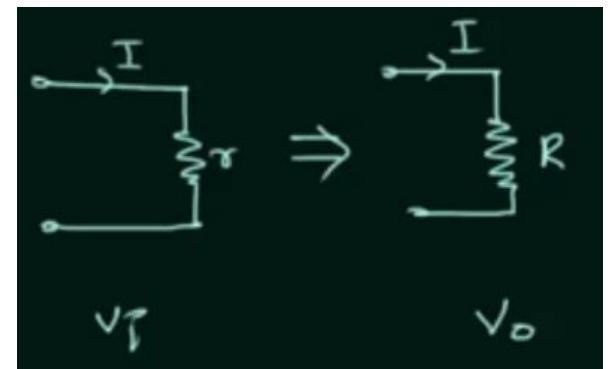
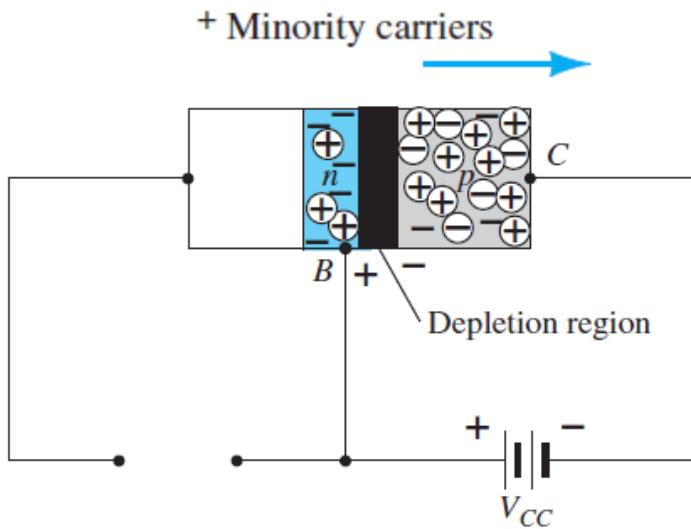


Active mode  
 $J_1 \rightarrow f.b.$   $R_{es} = 0$   
 $J_2 \rightarrow r.b.$   $R_{es} = \infty$

## Basic mechanism

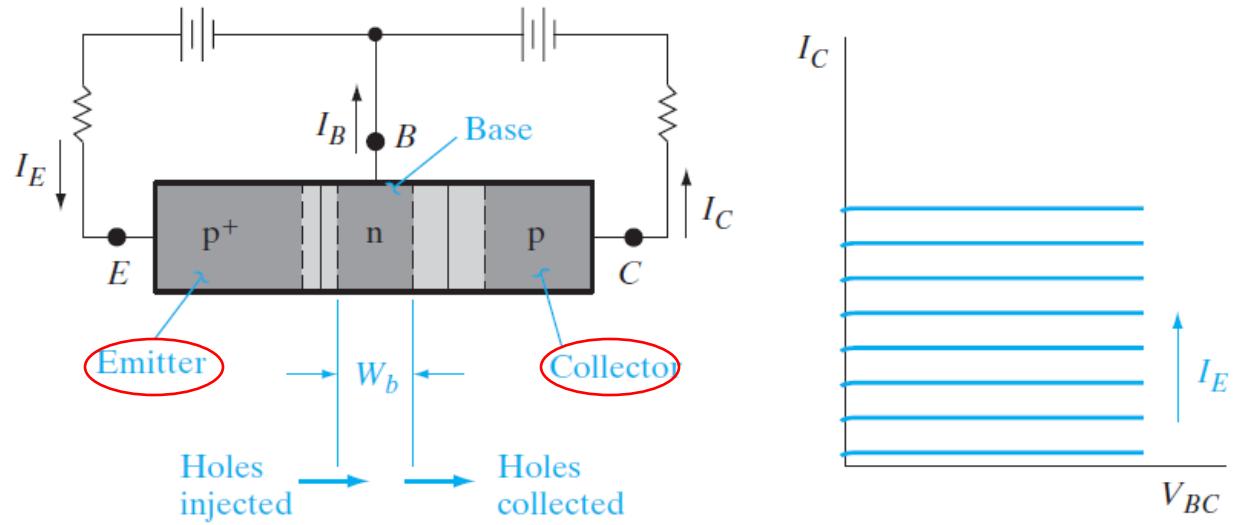


One p-n junction is forward biased,  
the other one is reverse biased.



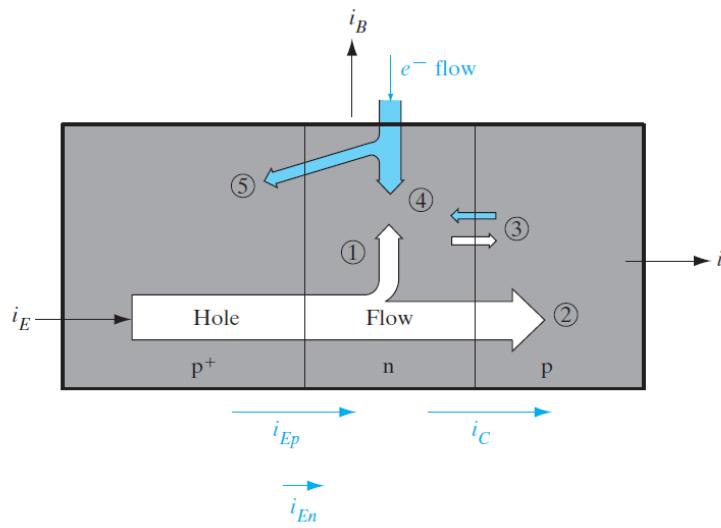
$$V_i = I \times R_i \quad V_o = I \times R_o$$
$$V_i < V_o \quad (\text{amplification})$$

# Understanding BJT IV characteristics...



- To have a good p-n-p transistor, we would prefer that almost all the holes injected by the emitter into the base be collected.
- Thus, the n-type base region should be narrow, and the hole lifetime  $t_p$  should be long. This requirement is summed up by specifying  $W_b \ll L_p$ .
- A second requirement is that the current  $I_E$  crossing the emitter junction should be composed almost entirely of holes injected into the base
  - Rather than electrons crossing from base to emitter.
  - This requirement is satisfied by doping the base region lightly compared with the emitter

## Current components in BJT



## Components of the base current

- Recombination of injected holes with electrons in the base, even with  $W_b < L_p$ . The electrons lost to recombination must be resupplied through the base contact.
- Some electrons will be injected from n to p in the forward-biased emitter junction, even if the emitter is heavily doped compared with the base.
- Some electrons are swept into the base at the reverse-biased collector junction due to thermal generation in the collector.

## Amplification with BJTs

$$i_C = Bi_{Ep}$$

- B is the fraction of injected holes which make it across the base to the collector. it is called the **base transport factor**.
- The total emitter current consists of hole component and electron component (injected from the base). The **emitter injection efficiency** is defined as:

$$\gamma = \frac{i_{Ep}}{i_{En} + i_{Ep}}$$

- **For an ideal transistor, we would like B and  $\gamma$  to be unity.**
- The relation between collector and emitter currents is:

$$\frac{i_C}{i_E} = \frac{Bi_{Ep}}{i_{En} + i_{Ep}} = B\gamma \equiv \alpha$$

The product  $B\gamma$  is defined as the factor  $\alpha$ , called the current transfer ratio.

## Amplification with BJTs contd...

- There is no real amplification between emitter and collector currents, since  $\alpha$  is smaller than unity.
- On the other hand, the relation between base current and collector current is more promising.
- The base current consists of mainly two parts: **electrons recombining with holes in the base, electrons injected across the forward bias junction:**

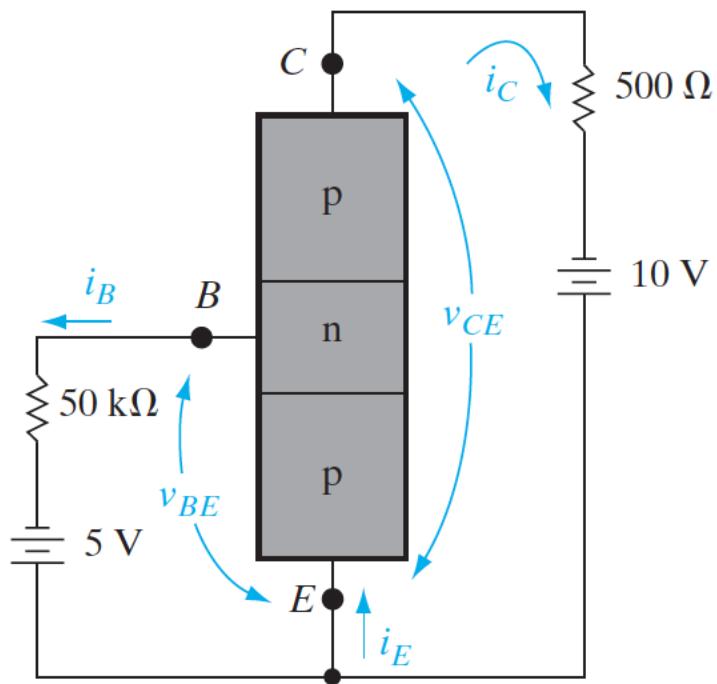
$$i_B = i_{En} + (1-B)i_{Ep}$$

- The relation between collector and base current is:  
$$\frac{i_C}{i_B} = \frac{Bi_{Ep}}{i_{En} + (1 - B)i_{Ep}} = \frac{B[i_{Ep}/(i_{En} + i_{Ep})]}{1 - B[i_{Ep}/(i_{En} + i_{Ep})]}$$
  
$$\frac{i_C}{i_B} = \frac{B\gamma}{1 - B\gamma} = \frac{\alpha}{1 - \alpha} \equiv \beta$$
- The factor  $\beta$  relating the collector current to the base current is the *base-to-collector current amplification factor*.
- Since  $\alpha$  is near unity, it is clear that  $\beta$  can be large for a good transistor, and the collector current is large compared with the base current.

**But, how can the collector current  $i_C$  can be controlled by variations in the small current  $i_B$ ?**

- It can be shown from space charge neutrality arguments that  $i_B$  can indeed be used to determine the magnitude of  $i_C$ .
- Since the n-type base region is electrostatically neutral between the two transition regions, the presence of excess holes in transit from emitter to collector calls for compensating excess electrons from the base contact.

- There is an important difference in the times that electrons and holes spend in the base.
- The average excess hole spends a time  $\tau_t$ , defined as the transit time from the emitter to collector.
- Since the base width  $W_b$  is made small compared with  $L_p$ , this transit time is much less than the average hole lifetime  $\tau_p$  in the base.
- On the other hand, an average excess electron supplied from the base contact spends  $\tau_p$  seconds in the base, ensuring space charge neutrality during the lifetime of an average excess hole.
- While the average electron waits  $\tau_p$  seconds for recombination, many individual holes can enter and leave the base region, each with an average transit time  $\tau_t$ .
- In particular, for each electron entering from the base contact,  $\tau_p / \tau_t$  holes can pass from the emitter to collector while maintaining space charge neutrality.
- 
- Thus the ratio of collector current to base current is simply: 
$$\frac{i_C}{i_B} = \beta = \frac{\tau_p}{\tau_t}$$



$$\tau_p = 10 \mu\text{s}$$

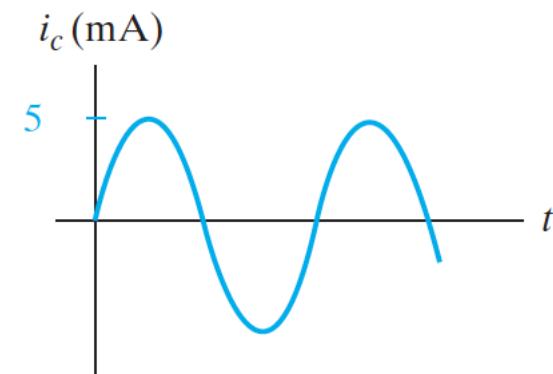
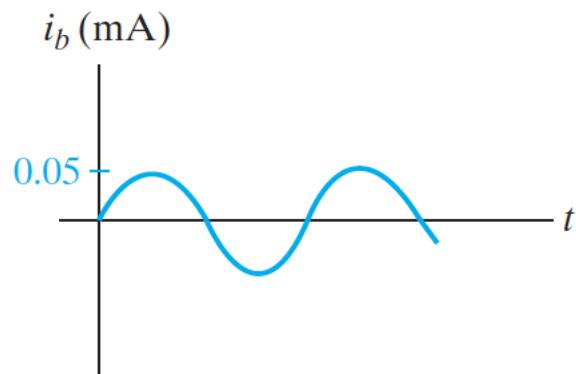
$$\tau_t = 0.1 \mu\text{s}$$

$$\frac{i_C}{i_B} = \beta = \frac{\tau_p}{\tau_t} = 100$$

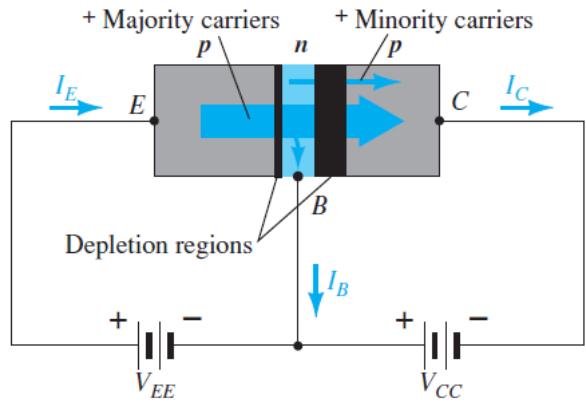
Neglecting  $v_{BE}$

$$I_B = \frac{5 \text{ V}}{50 \text{ k}\Omega} = 0.1 \text{ mA}$$

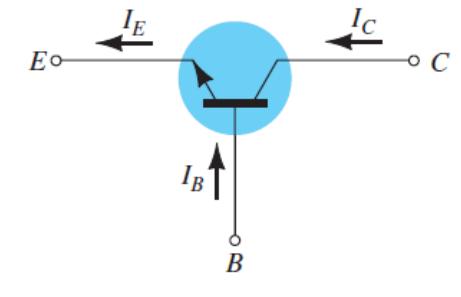
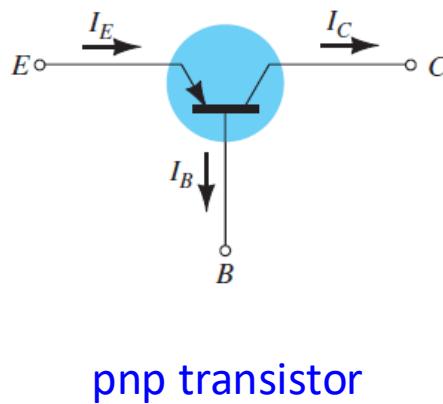
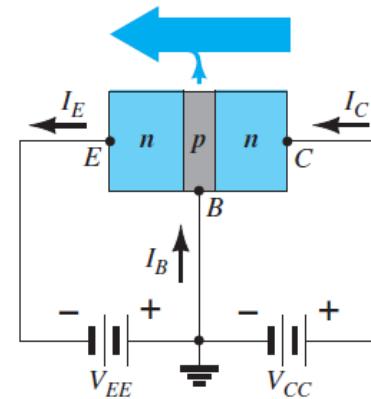
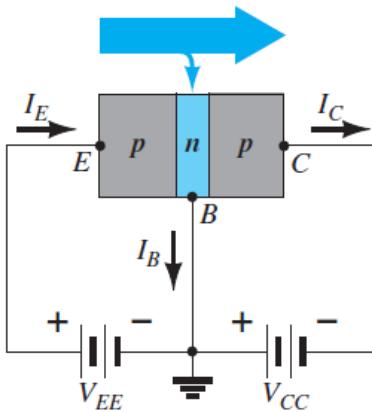
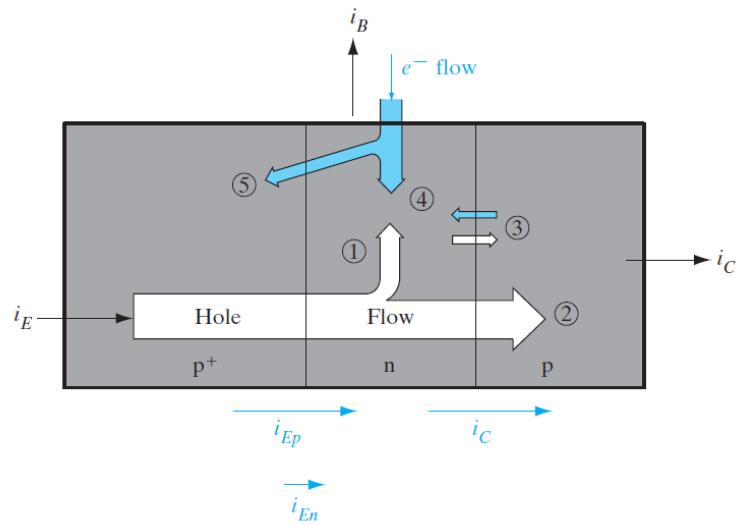
$$I_C = \beta I_B = 10 \text{ mA}$$



# Bipolar Junction Transistor (BJT)



## Current components in BJT



## Different regimes of operation of BJT

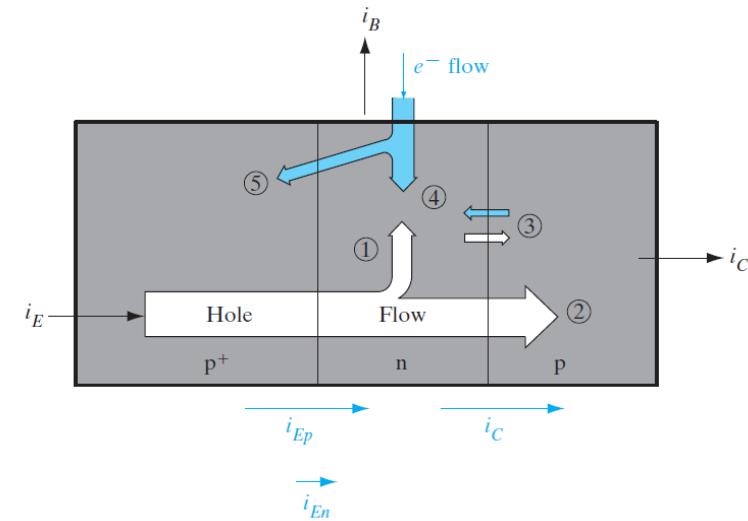
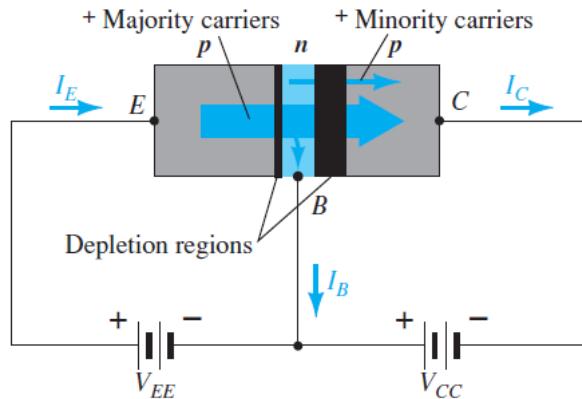
Inverse active regime

Active regime

Cut-off regime

Saturation regime

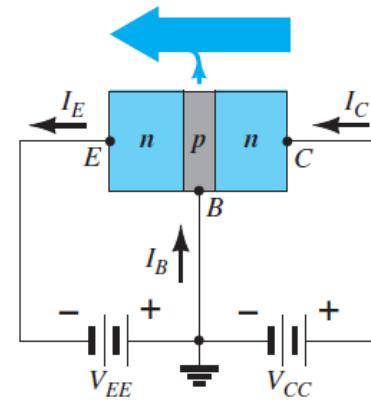
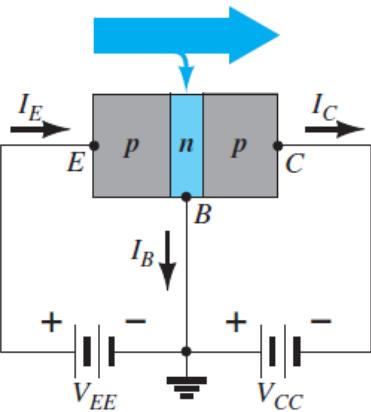
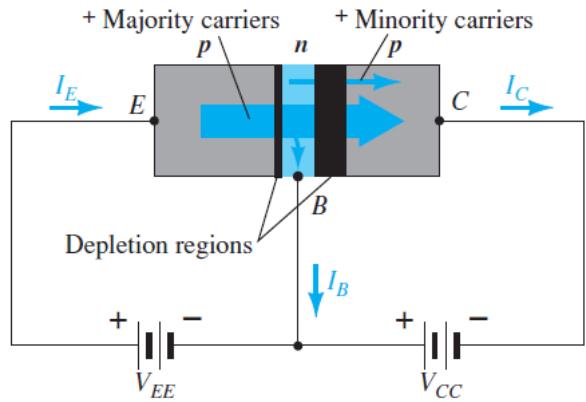
# BJT Currents: Review



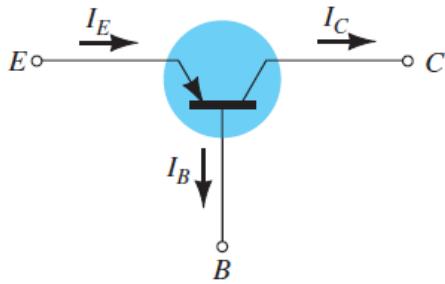
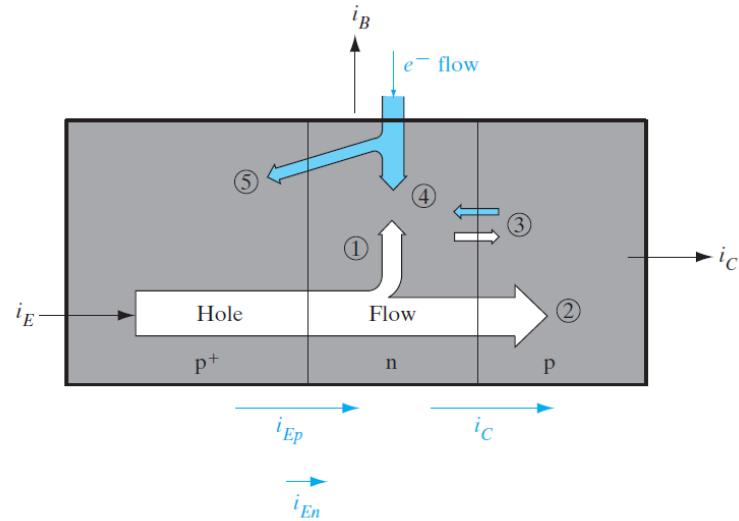
$$\frac{i_C}{i_E} = \frac{Bi_{Ep}}{i_{En} + i_{Ep}} = B\gamma \equiv \alpha$$

$$\frac{i_C}{i_B} = \frac{B\gamma}{1 - B\gamma} = \frac{\alpha}{1 - \alpha} \equiv \beta$$

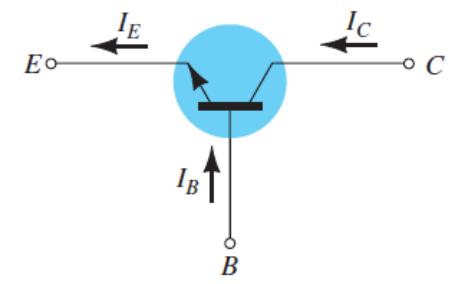
# Bipolar Junction Transistor (BJT)



## Current components in BJT



npn transistor



pnp transistor

## Different regimes of operation of BJT

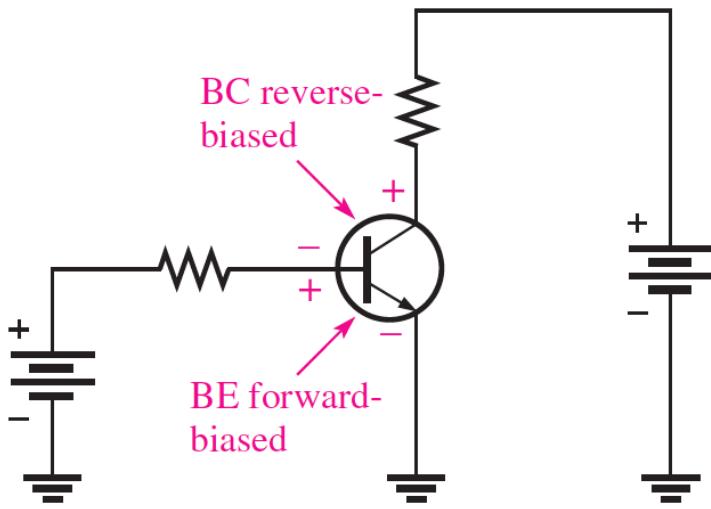
Active regime

Inverse active regime

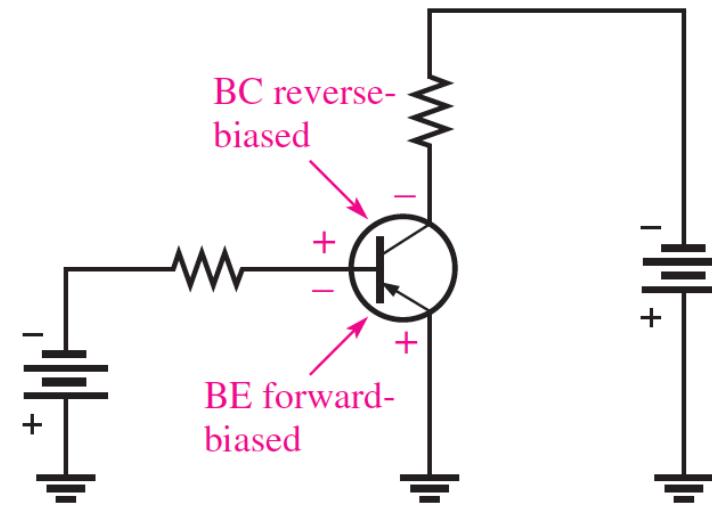
Cut-off regime

Saturation regime

# BJT Biasing



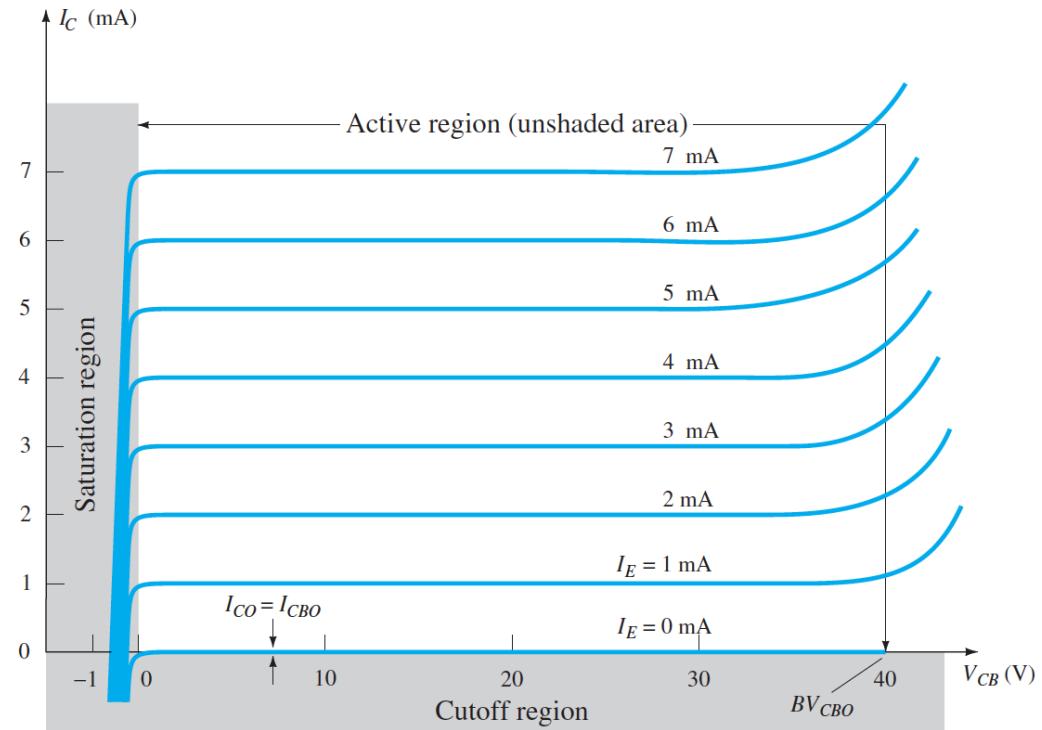
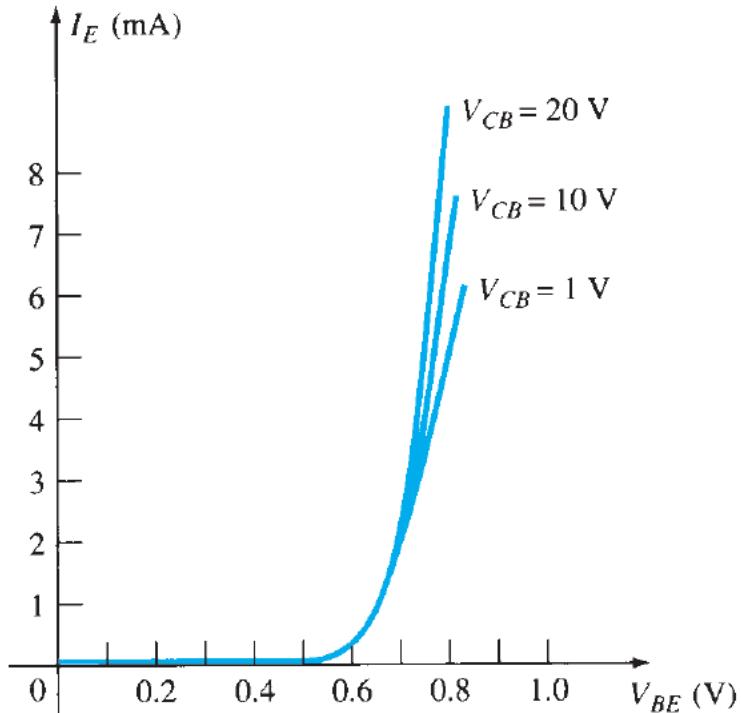
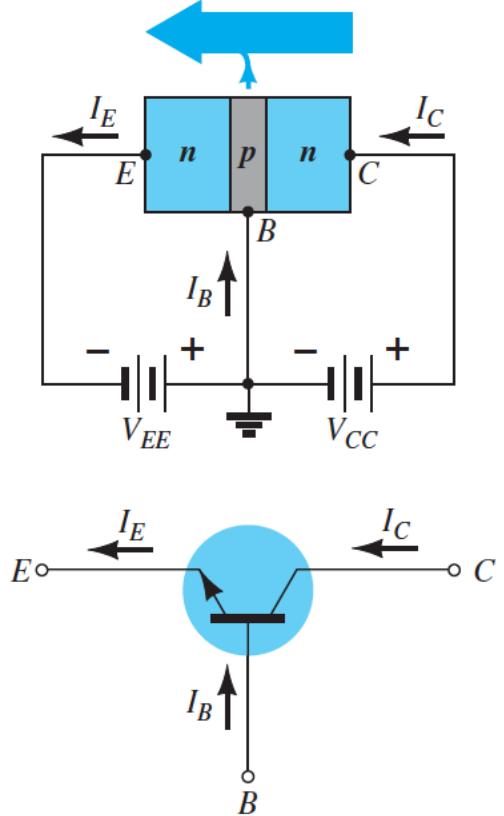
(a) *npn*



(b) *pnp*

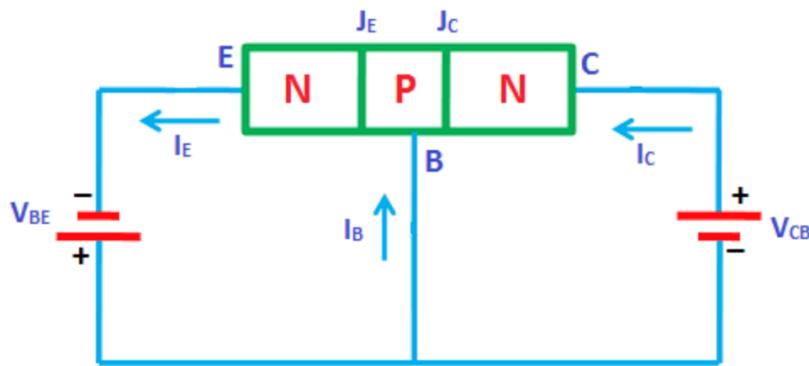
Forward-reverse bias of a BJT

## Bipolar Junction Transistor (BJT): Input and Output Characteristics

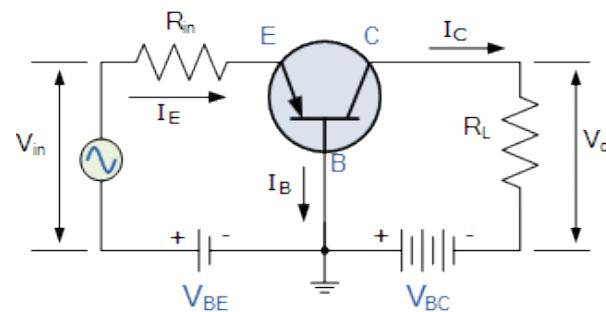


## Common Base (CB) Configuration

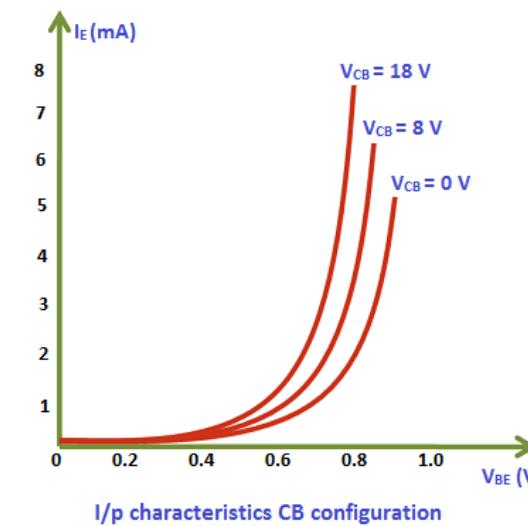
# BJT Configurations



no current gain but voltage gain

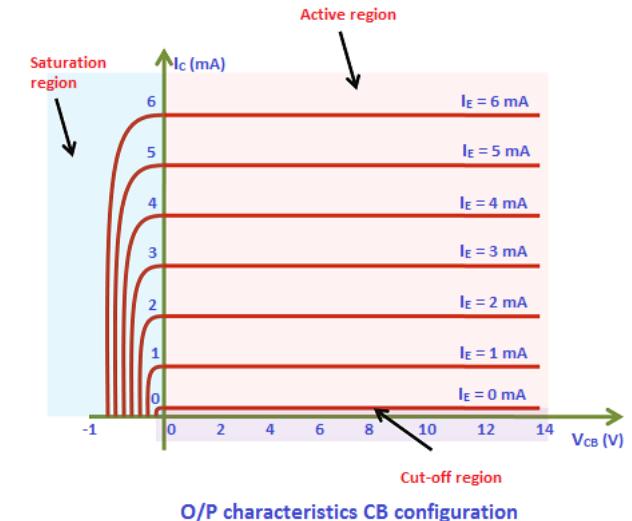


### Input characteristics



$I_E$  vs.  $V_{BE}$

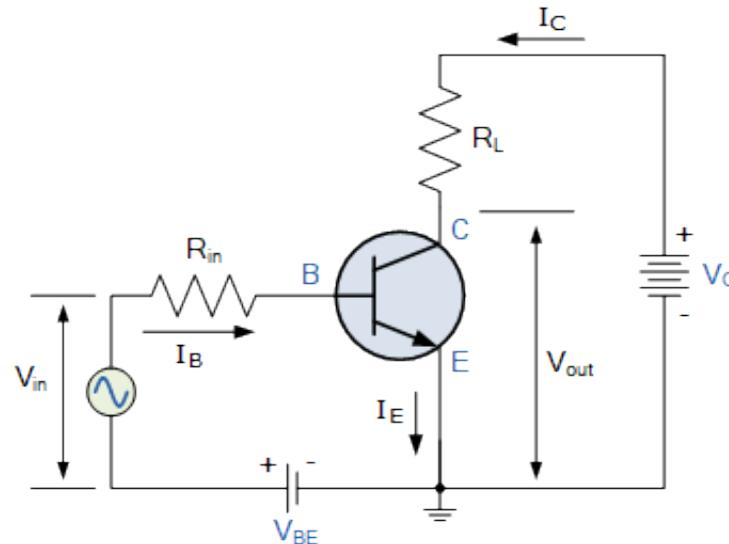
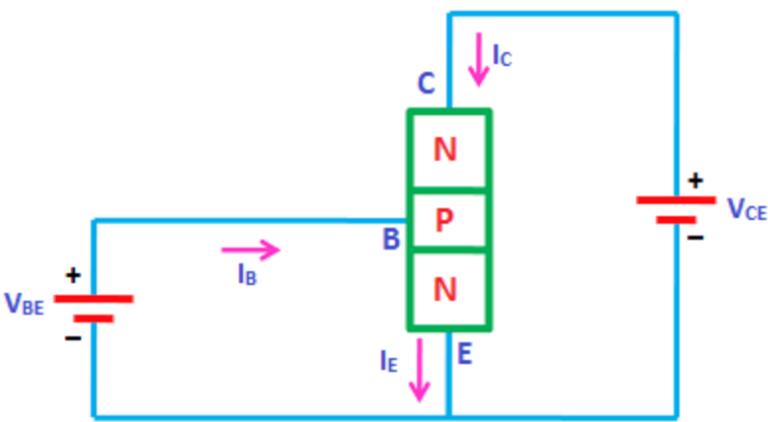
### Output characteristics



$I_C$  vs.  $V_{CB}$

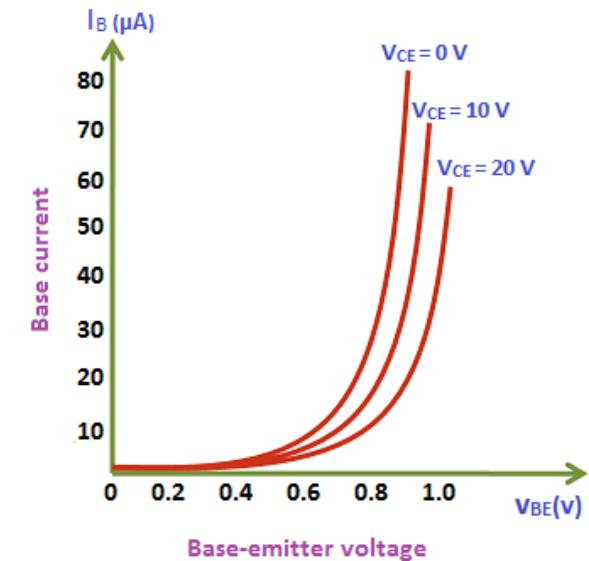
# BJT Configurations

## Common Emitter (CE) Configuration

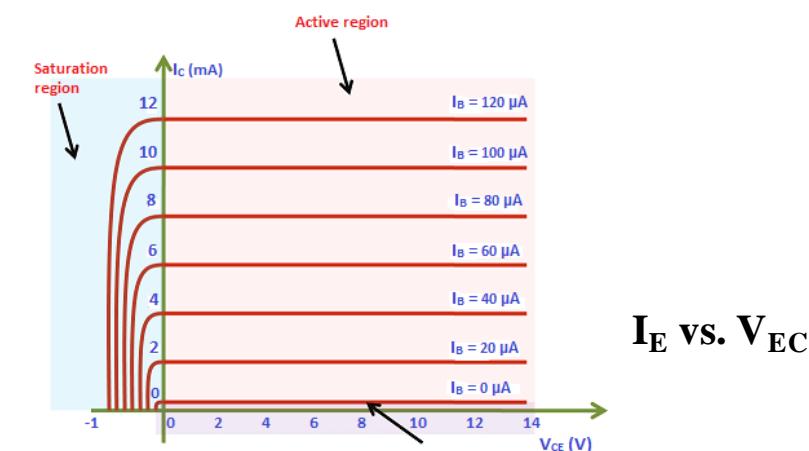


current gain and voltage gain

## Input characteristics



I/P characteristics CE configuration

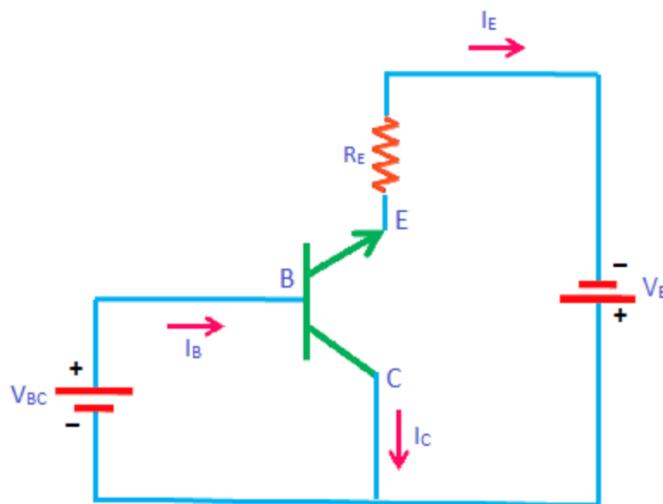
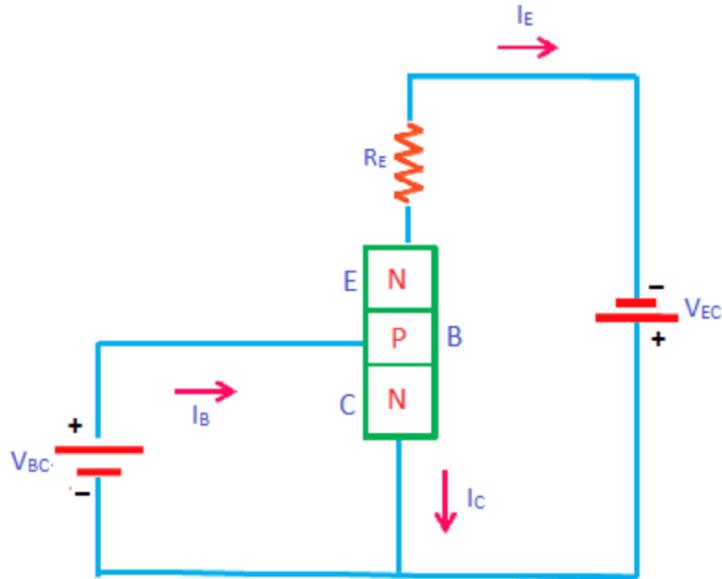


$I_C$  vs.  $V_{CE}$

## Output characteristics

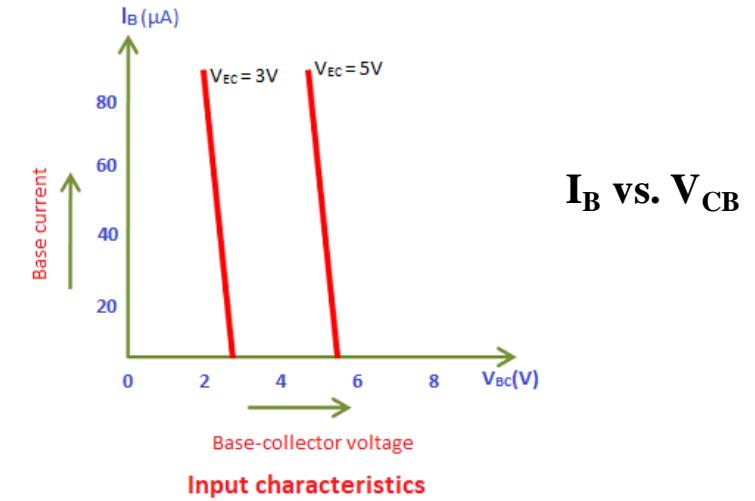
## Common Collector (CC) Configuration

# BJT Configurations

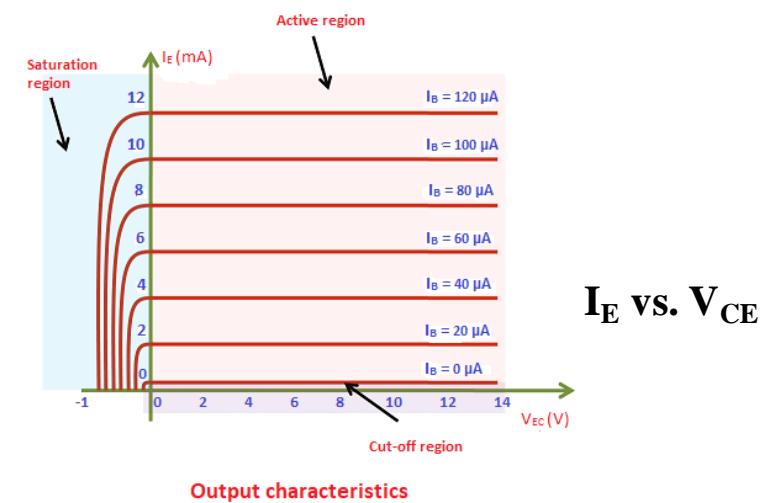


current gain but no voltage gain

### Input characteristics



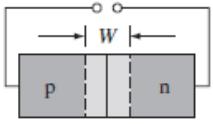
### Output characteristics



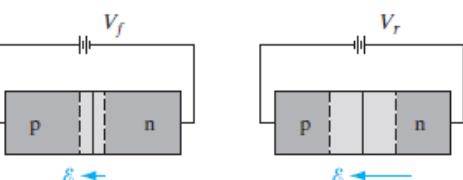
# Summary of electronic devices

## Diodes

Equilibrium  
( $V = 0$ )



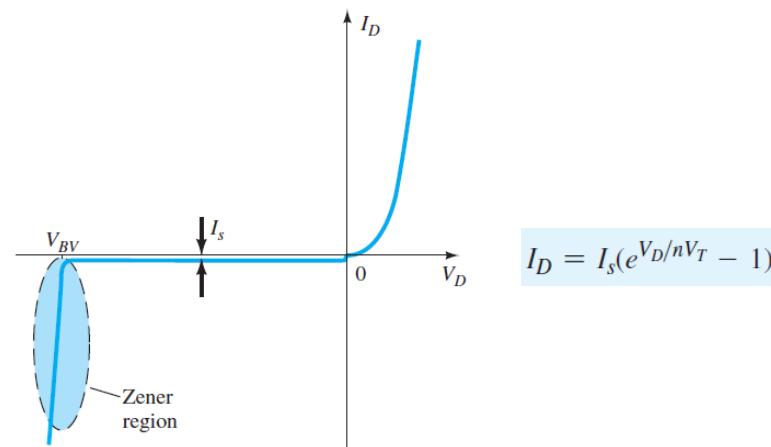
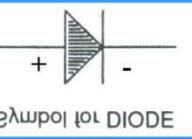
Forward bias  
( $V = V_f$ )



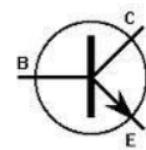
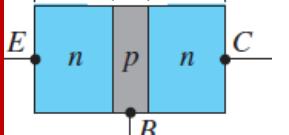
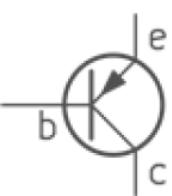
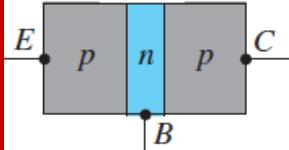
Reverse bias  
( $V = -V_r$ )



DIODE



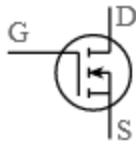
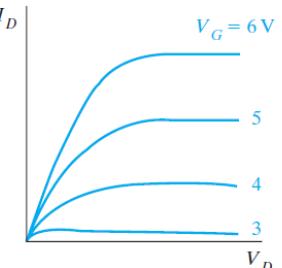
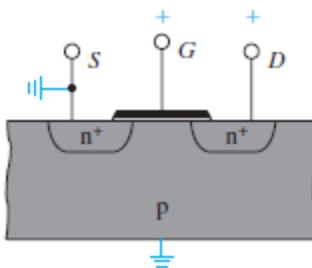
## BJTs



## BJT Configurations

- CB
- CC
- CE

## MOSFETs



# Integration

- Integration is the process of creating an integrated circuit (IC) by combining thousands of transistors into a single chip.

**SSI** - Small Scale integration

less than 100 components (about 10 gates)

**MSI** - Medium Scale integration

less than 500 components (more than 10 but less than 100 gates)

**LSI** - Large Scale integration

components b/w 500 and 300000 (more than 100 gates)

**VLSI** - Very Large Scale integration

it contains more than 300000 components per chip

**Nowadays, more than a billion transistor on a chip.**

Very large-scale integration (VLSI) is the process of integrating or embedding hundreds of thousands of transistors on a single silicon semiconductor microchip.

A microprocessor is an example of VLSI circuit.

# Why VLSI?

- Physically smaller size
- Integration improves the design
- Lower parasitic = higher speed
- Lower power consumption
- Integration reduces manufacturing cost - (almost) no manual assembly

## A Few VLSI companies in India

### 1 | Texas Instruments

Corporate office – Dallas, United States | Establishment – 1951 |

### 2 | Analog Device Inc.

Corporate office – Norwood, USA | Establishment – 1965 |

### 3 | Cypress Semiconductor Corporation

Corporate office – San Jose, USA | Establishment – 1982 |

### 4 | Broadcom Corporation

Corporate office – Irvine, USA | Establishment – 1991 |

### 5 | Cisco Systems

Corporate office – San Jose, USA | Establishment – 1984 |

### 6 | Bit Mapper Integration Technologies Private Limited

Corporate office – Pune, Maharashtra | Establishment – 1985 |

### 7 | Horizon Semiconductors

Corporate office – Bangalore, Karnataka | Establishment – 1815 |

### 8 | Einfochips limited

Corporate office – Ahmadabad, Gujarat | Establishment – 1994 |

### 9 | Trident Tech Labs

Corporate office – New Delhi, India | Establishment – 2000 |

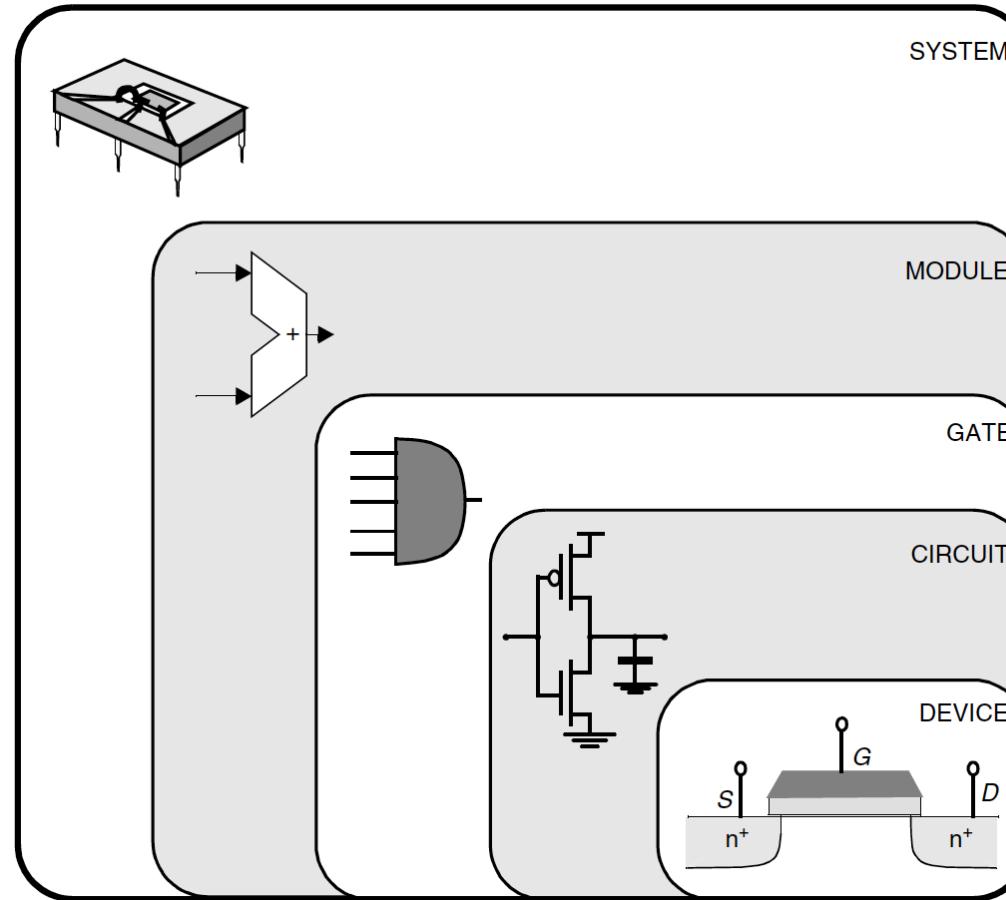
### 10 | HCL technologies

Corporate office – Noida, Uttar Pradesh | Establishment – 1991 |

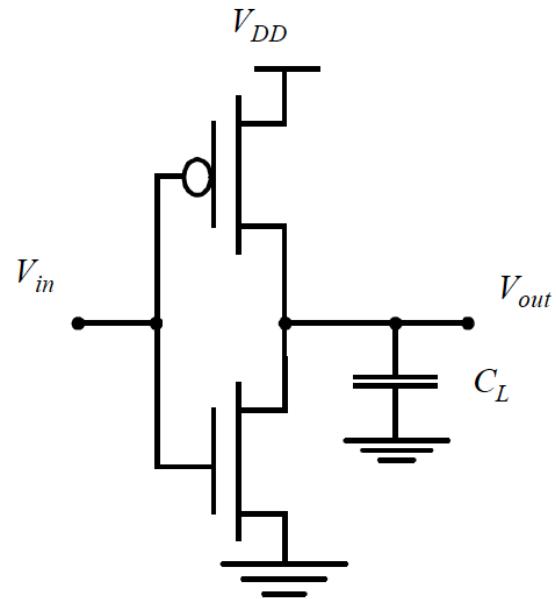
# **System Level Electronics**

## **Abstraction**

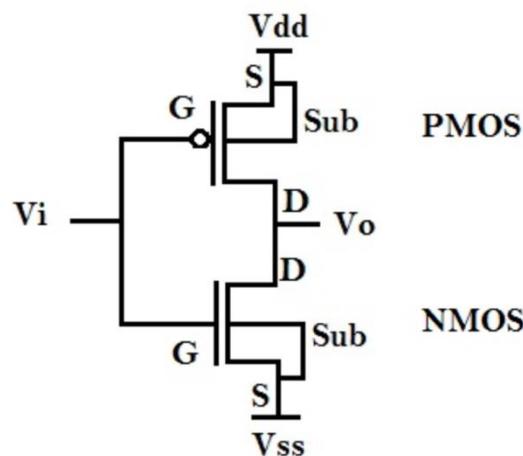
# Design abstraction in digital electronics



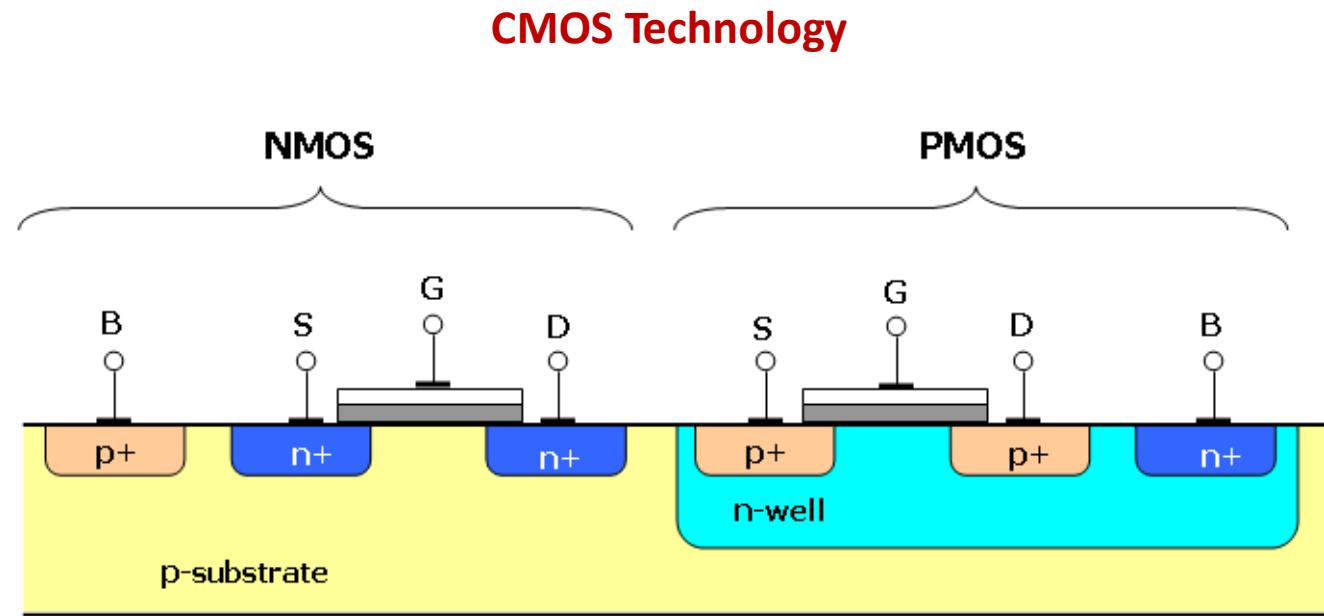
# Logic gate implementation – CMOS Inverter



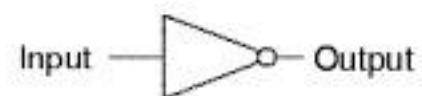
CMOS Inverter



**G** = Gate Terminal  
**S** = Source Terminal  
**D** = Drain Terminal  
**Sub** = Substrate Terminal

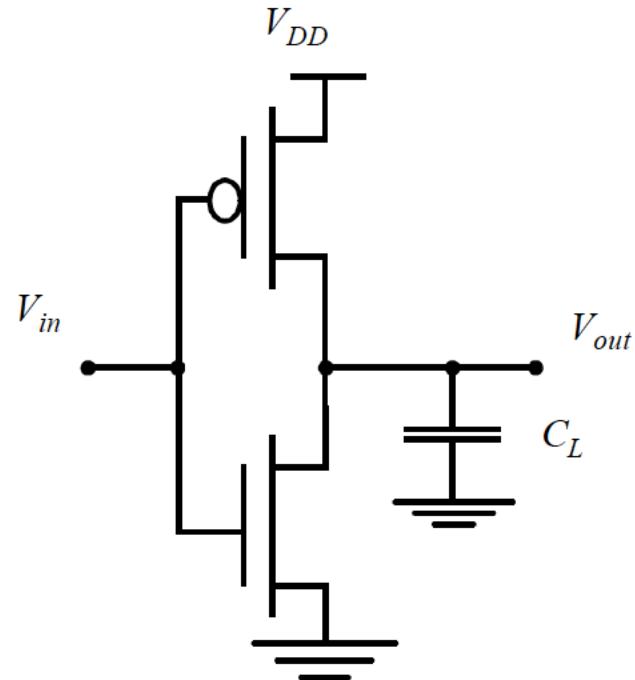


CMOS Technology



Input	Output
1	0
0	1

# CMOS Inverter



Pull Up

Pull Down

- Cost
- Static behavior
- Dynamic behavior/performance
- Energy efficiency

CMOS Inverter

**Thank you**